

2812

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IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re application of: Okino et al.

Art Unit: 2812

Application No. 09/997,646

Filed: November 28, 2001

For: APPARATUS AND METHODS FOR
BLOCKING HIGHLY SCATTERED CHARGED
PARTICLES IN A PATTERNED BEAM IN A
CHARGED-PARTICLE-BEAM
MICROLITHOGRAPHY SYSTEM

Examiner: Not yet assigned.

Date: April 30, 2002

CERTIFICATE OF MAILING

I hereby certify that this paper and the documents referred to as being attached or enclosed herewith are being deposited with the United States Postal Service on April 30, 2002 as First Class Mail in an envelope addressed to: COMMISSIONER FOR PATENTS, WASHINGTON, D.C. 20231.

Donald L. Stephens Jr.
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GB
3/4/03

INFORMATION DISCLOSURE STATEMENT
PURSUANT TO 37 C.F.R. § 1.97(b)

COMMISSIONER FOR PATENTS
WASHINGTON, DC 20231

Sir:

Listed on the accompanying form PTO-1449 and enclosed herewith are two English-language documents. Applicants respectfully request that these documents be listed as references cited on the issued patent.

Applicants filed this Information Disclosure Statement ("IDS") within three months of the filing date of a national application, within three months of the date of entry of the national stage as set forth in § 1.491 in an international application, before the mailing date of a first Office action on the merits, or before the mailing of a first Office action after the filing of request for continued examination under § 1.114. As a result, no fee should be required to file this IDS. However, if the Patent Office determines that a fee is required for Applicants to file this Information Disclosure Statement, please charge any such fees, or credit overpayment, to Deposit Account No. 02-4550. A **duplicate** copy of this Information Disclosure Statement is enclosed.

Respectfully submitted,

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INFORMATION DISCLOSURE STATEMENT BY APPLICANT				Docket: 4641-61349		App: 09/997,646	
				Applicant: Okino et al.			
				Filed: November 28, 2001		Art Unit: 2812	
U.S. PATENT DOCUMENTS							
Init.*		Number	Date	Name	Class	Sub	Filed
		5,130,213	7/14/1992	Berger et al.			
FOREIGN PATENT DOCUMENTS							
		Number	Date	Country	Class	Sub	
OTHER DOCUMENTS							
			Koops et al., "Submicron Lithography by Demagnifying Electron-Beam Projection," in Schmahl et al., <i>X-Ray Microscopy, Springer Series in Optical Sciences Vol. 43</i> :118- 129, Springer Verlag, Berlin, 1984.				
			<div style="text-align: right;"> RECEIVED MAY 13 2002 CL TECHNICAL CENTER 2800 </div>				
EXAMINER:				DATE			
*Examiner: Initial if considered, whether or not in conformance with MPEP 609; draw line through cite if not in conformance and not considered. Send copy.							